

Single photon processing at high rate with pixel detectors from particle physics

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**WORKSHOP on
DETECTORS for
SYNCHROTRON RESEARCH**

WASHINGTON

30-31 Oct 2000



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CONTENTS

TRACKING PIXEL DETECTORS

2 SYSTEMS IN USE

SPECIFICATIONS

COMPLEXITY inside PIXEL

SIGNAL PROCESSING

LOGIC, TEST, CONTROL

PHOTON COUNTING PIXELS

SMALL AREA -> RATE

SIMPLE EXTENSION

RESULTS PCC1 at CERN

SPECIFIC NEEDS SYNCHROTRON

DEEP SUBMICRON IC

ASSEMBLY TECHNOLOGY



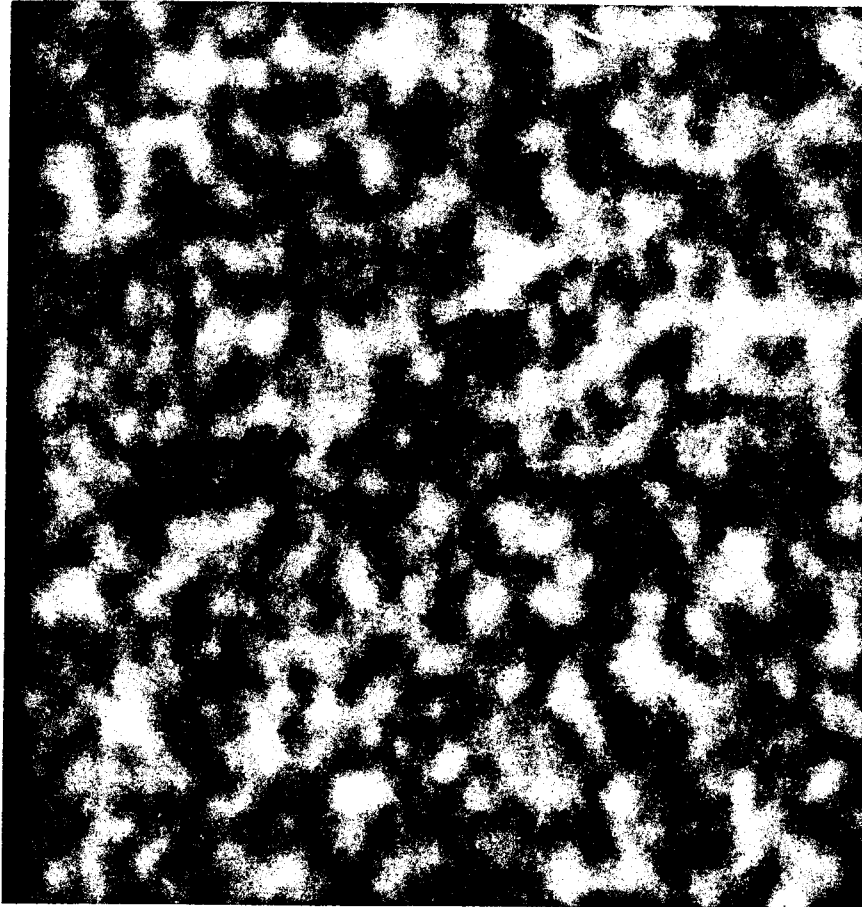
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FIXED TARGET EXPERIMENT HEAVY-ION EVENT

Pb ion in OMEGA spectrometer



RD19

WA97

TRACKING using PIXEL DETECTOR TELESCOPE



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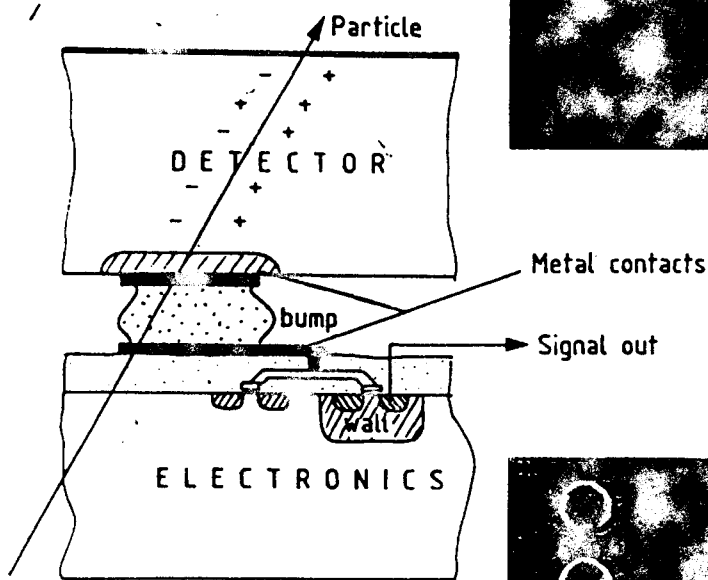
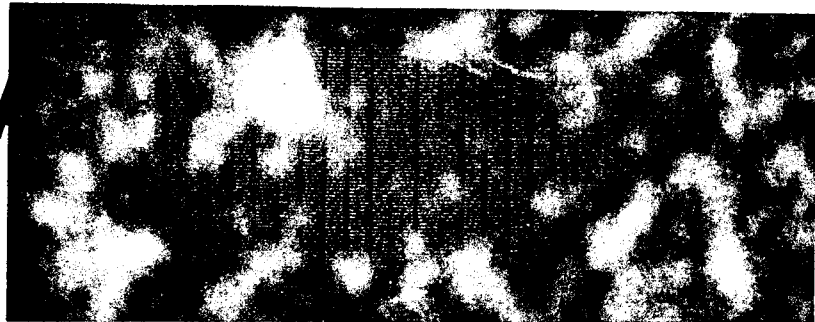
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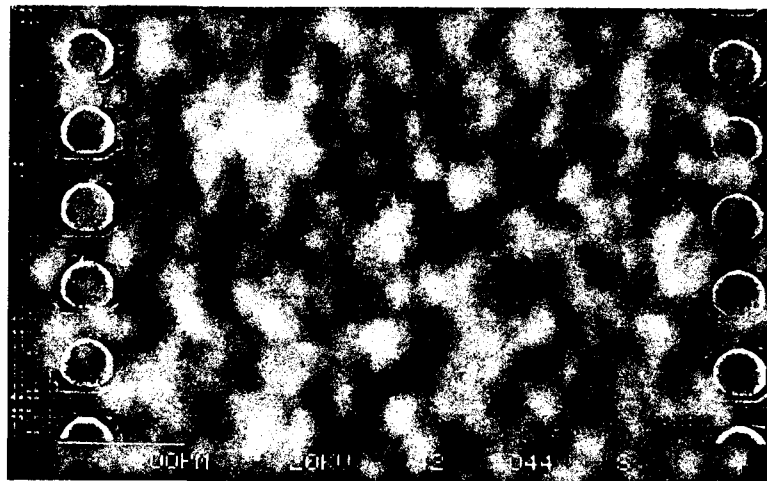
PIXELS in PARTICLE PHYSICS

HYBRID Si SENSOR

SENSOR MATERIAL
Si



BUMPS



READOUT ELECTRONICS



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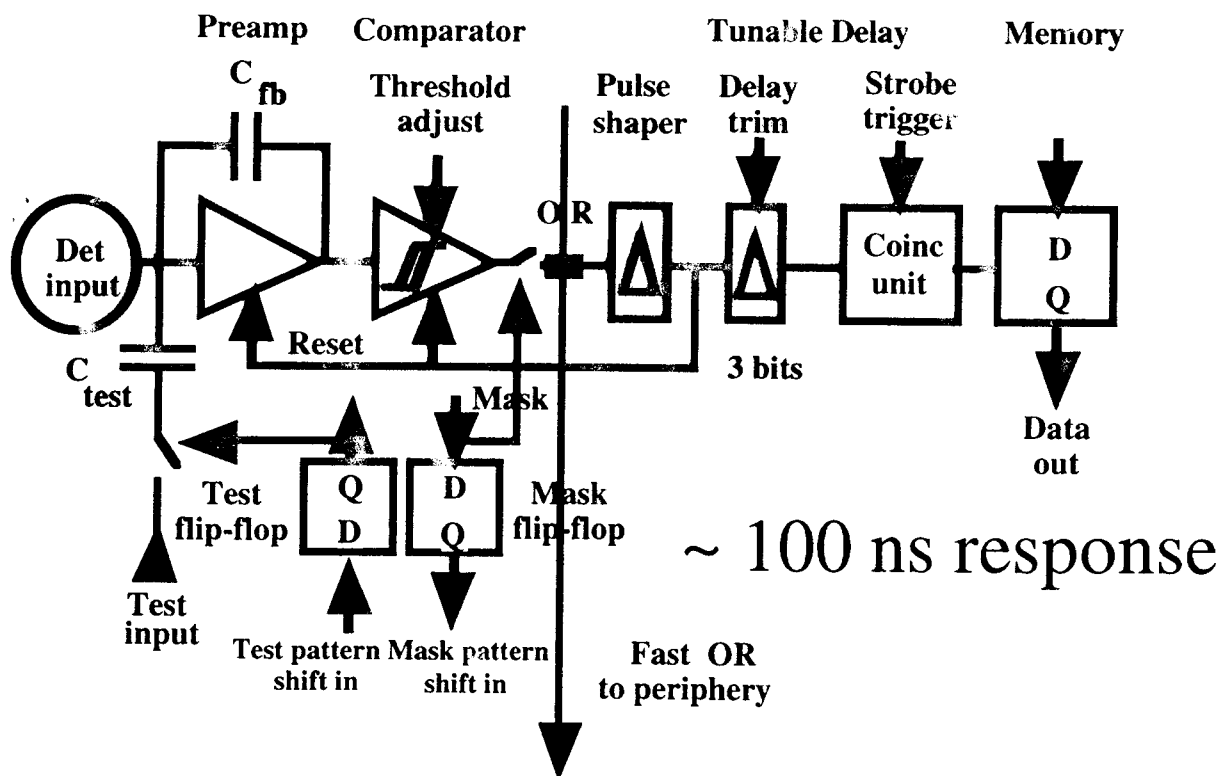
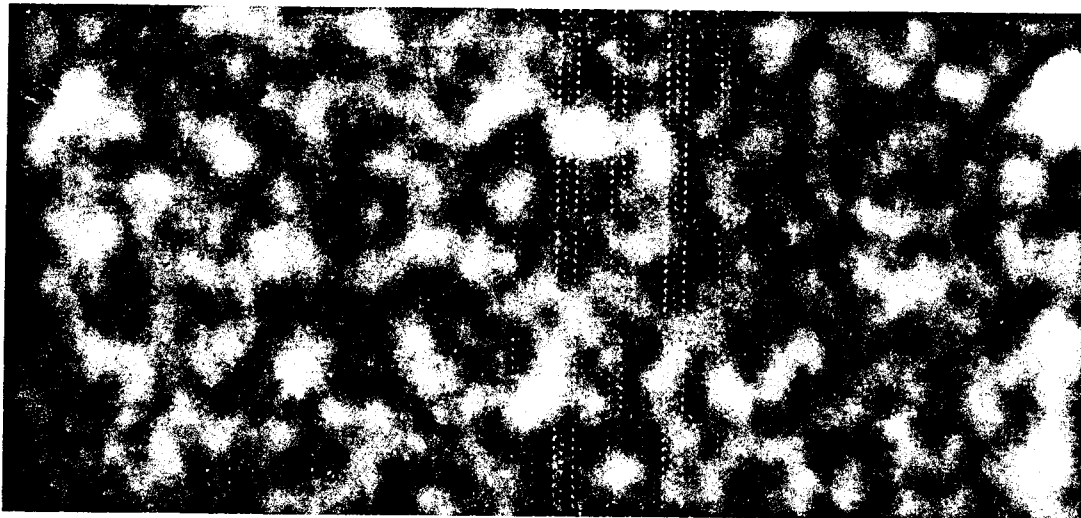
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PIXELS in PARTICLE PHYSICS

Chips at CERN

LHC1 PIXEL READOUT $50\mu\text{m} \times 500\mu\text{m}$



ELECTRONICS DIAGRAM SINGLE PIXEL



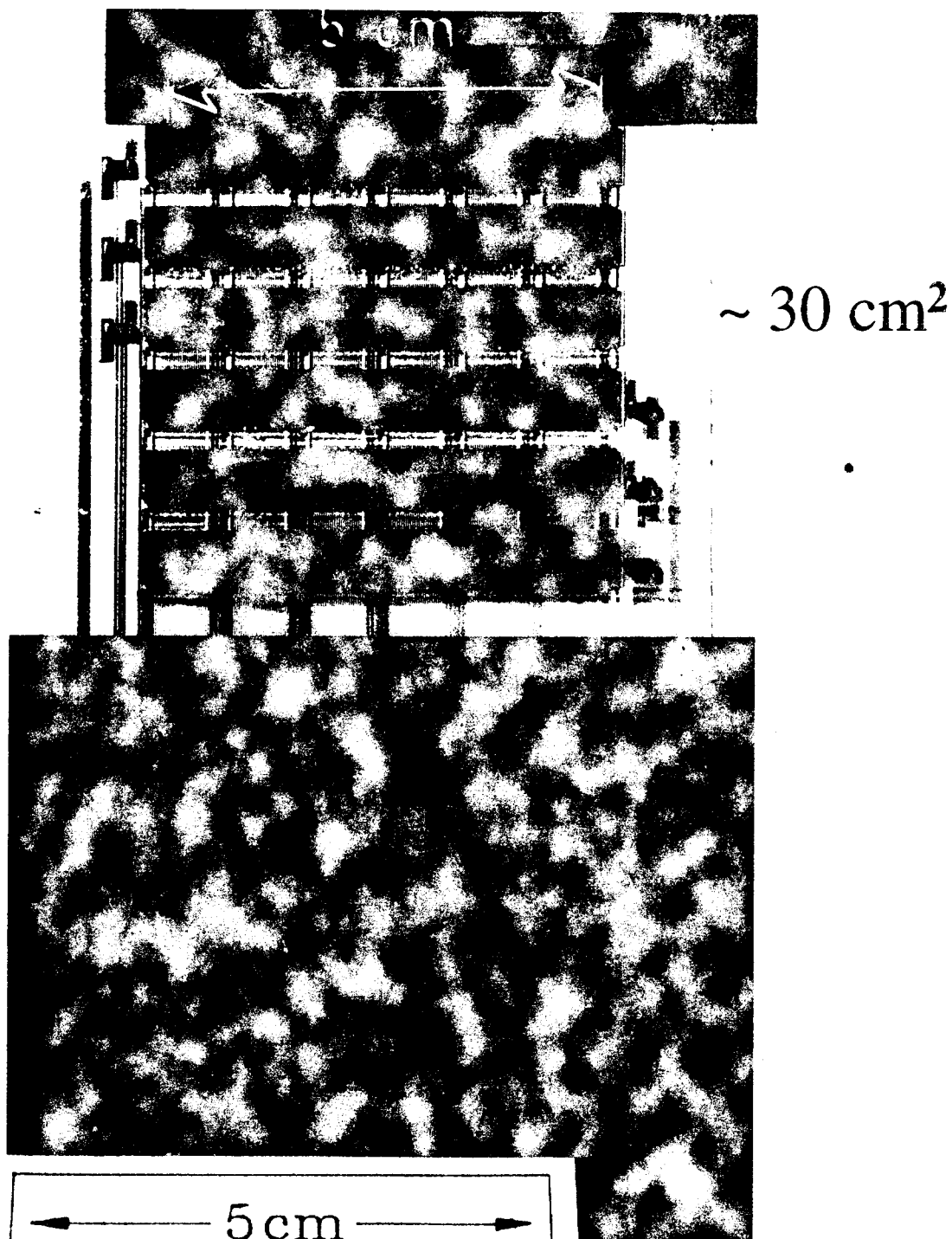
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'REACTIVE' PIXELS at CERN

ARRAY of 6 LADDERS, 36 CHIPS



VIEW of LADDERS and CHIPS

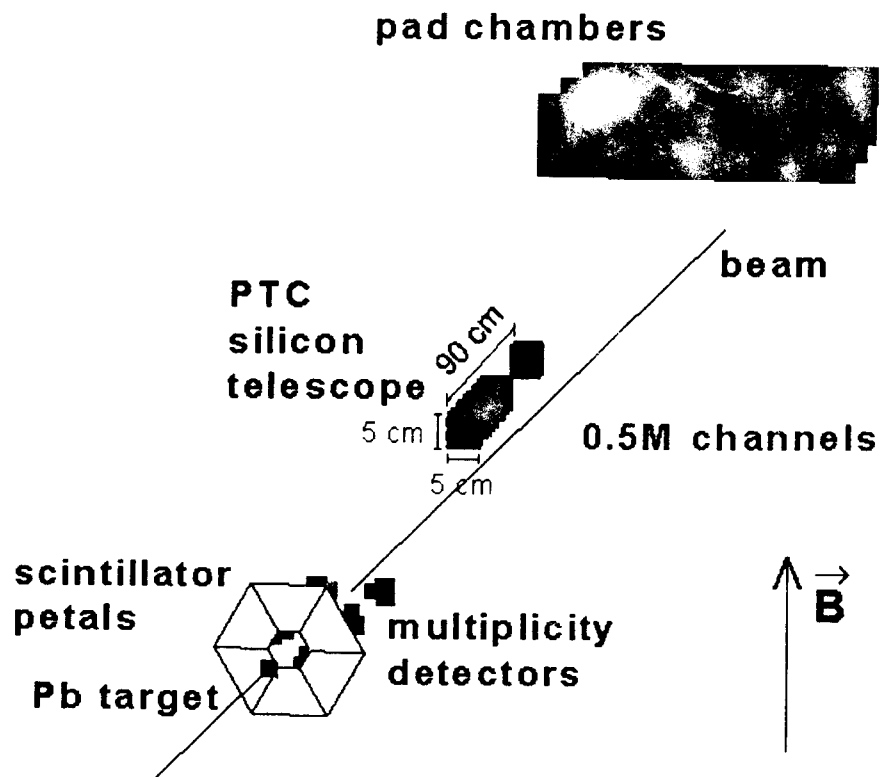


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WA97 set-up in the Omega magnet



PIXEL TELESCOPE

CHIPS -> LADDERS ->

ARRAYS -> PLANES

4, 7, 14 PLANES IN USE



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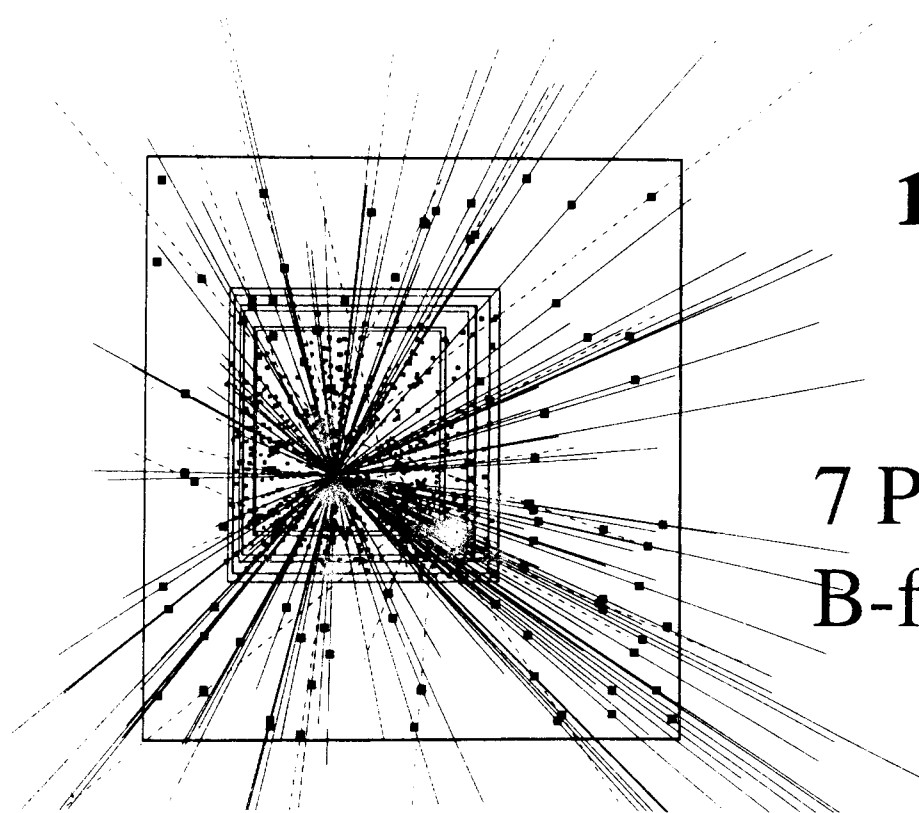
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TRACKING with PIXELS at CERN

WA97

RD19



153 tracks

7 PLANES
B-field OFF

^{208}Pb ion at 158 GeV A on Pb target

Millions of EVENTS ANALYZED

SPACE POINTS
NOISE-FREE



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PIXELS in PARTICLE PHYSICS

2 SYSTEMS at CERN

WA97-NA57 HEAVY-ION EXP

14 PLANES USED, 800 CHIPS, 400 cm²

1994 - now

DELPHI e - p COLLIDER EXP

4 CROWNS, 2500 CHIPS, 1400 cm²

1997 - now

several LHC EXPTS planned



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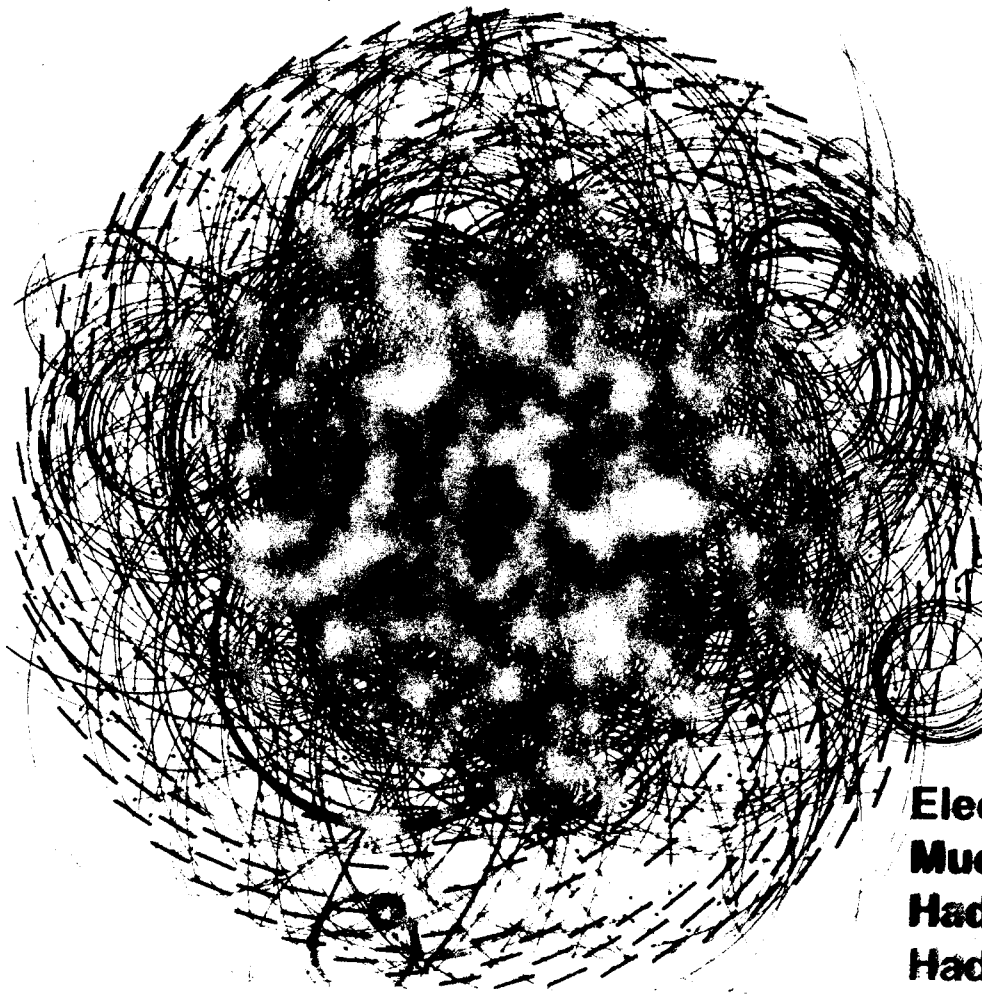


FUTURE PARTICLE PHYSICS EXPERIMENTS at CERN

HEAVY-ION & COLLIDER expts

HIGH MULTIPLICITY several 100s

HIGH RATE 40 MHz



CMS

$H \rightarrow \mu\mu\mu\mu$

$m(H) = 150 \text{ GeV}$

+ 20 Min bias



Electrons

Muons

Hadrons $pt < 2 \text{ GeV}$

Hadrons $pt > 2 \text{ GeV}$

**HIGHLY SEGMENTED, FAST,
RADHARD DETECTORS NEEDED**
SIGNAL in $100 \mu\text{m Si} : 8000 e^- \sim 30 \text{ keV}$



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ISSUES in TRACKING

2-D SEGMENTATION in PIXELS

SPACE POINTS $\sim 10 \mu\text{m}$

LOW CAPACITANCE $< 100 \text{ fF}$

-> NOISE $50 - 150 \text{ e}^- \text{ rms}$

-> THIN SENSOR $80 \mu\text{m} ?$

-> SPEED $\text{signal} < 10 \text{ ns}$

HIGH MULTIPLICITY

coincident particles

BINARY or ANALOG READOUT

INTERPOLATION

THRESHOLD SETTING

ALIGNMENT of MODULES

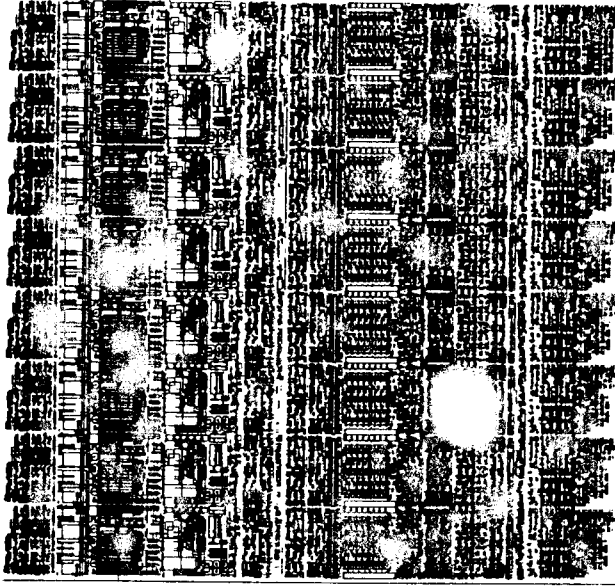
PIXELS easier than 1-D projection



FUTURE PIXEL DETECTORS

in PARTICLE PHYSICS

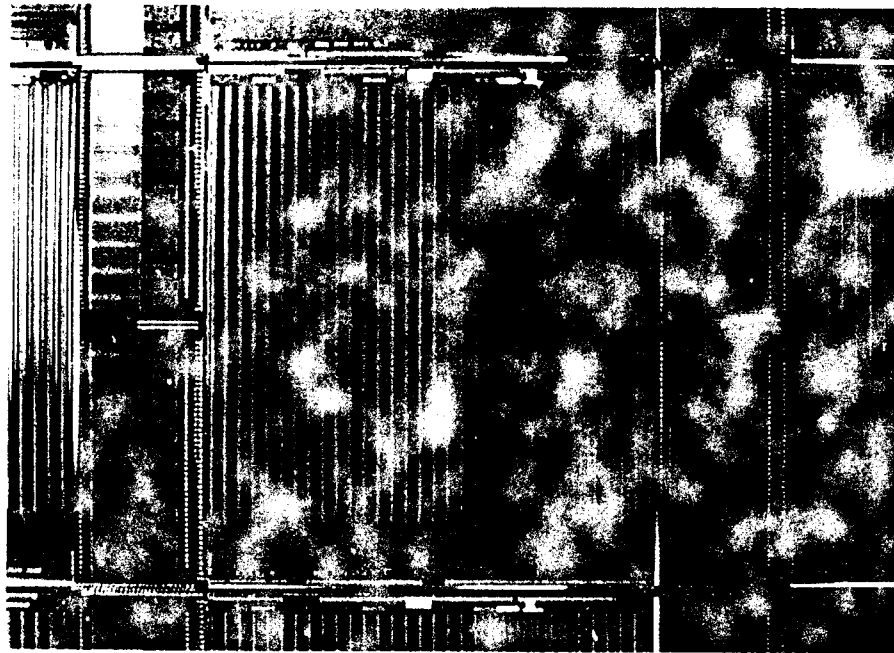
eg ALICE HEAVY-ION EXP



8 cells, blocked
radhard 30 Mrad

$400\mu\text{m} \times 425\mu\text{m}$

8000 pixels, 13 M transistors, 2.2 cm^2



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COMPLEXITY in PIXEL

**CMOS can be used for ANALOG
DENSITY**

LOW POWER

LOW NOISE

**SIGNAL PROCESSING on
SINGLE QUANTA**

CONTACTS with NEIGHBOURS

**COMPENSATE for
SENSOR IMPERFECTIONS**

TRIMMING GAIN, THRESHOLD

SYSTEM TEST, CONTROL

INTEGRATE ANCILLARY FUNCTIONS



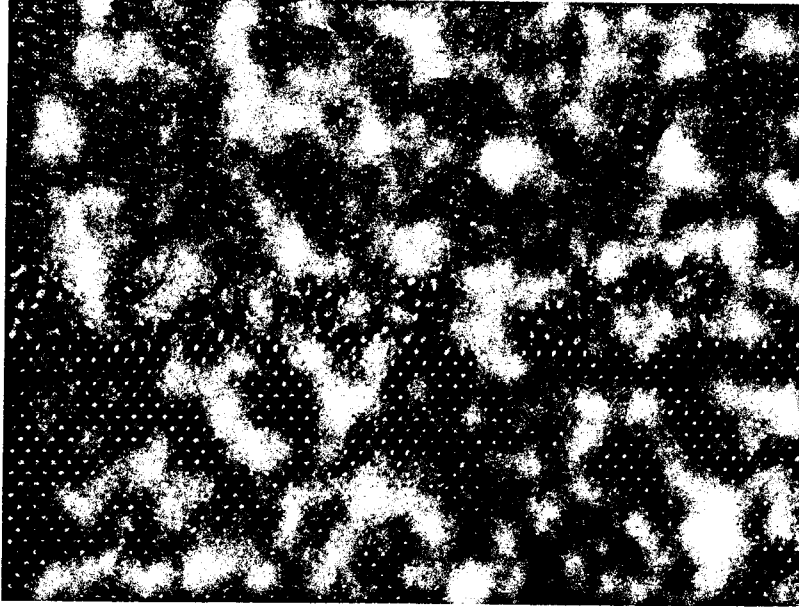
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Impact of Deep-submicron CMOS

MOS Gate TEM Bell Labs April 2000



Poly Si

SiO₂ 1.6 nm

Si

Reliable oxides can be made with
only ~ 6 atoms in SiO₂ layer

SiO₂ CMOS technology used
down to ~ 0.08 μm transistors

**Thin gate oxide (< 8 nm) also is
unaffected by radiation (test > 30 Mrad)**

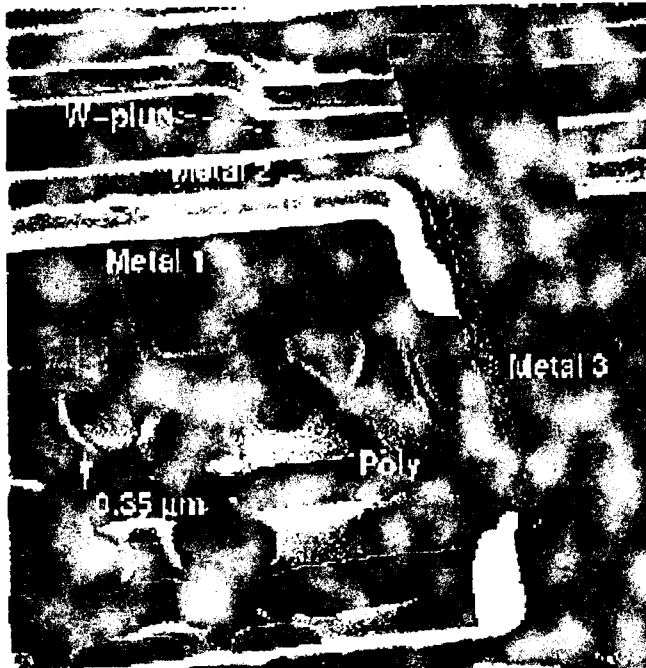


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PIXEL readout relies on Deep-submicron CMOS



Lucent Technologies
Bell Labs Innovations



poly Si gate

length $.35 \mu\text{m}$

3 metals shown

**Component density +
6 to 9 levels of interconnect**

Pixel chips at CERN now $0.25 \mu\text{m}$

**FUNCTIONS
LOW NOISE**

**SPEED
LOW POWER**



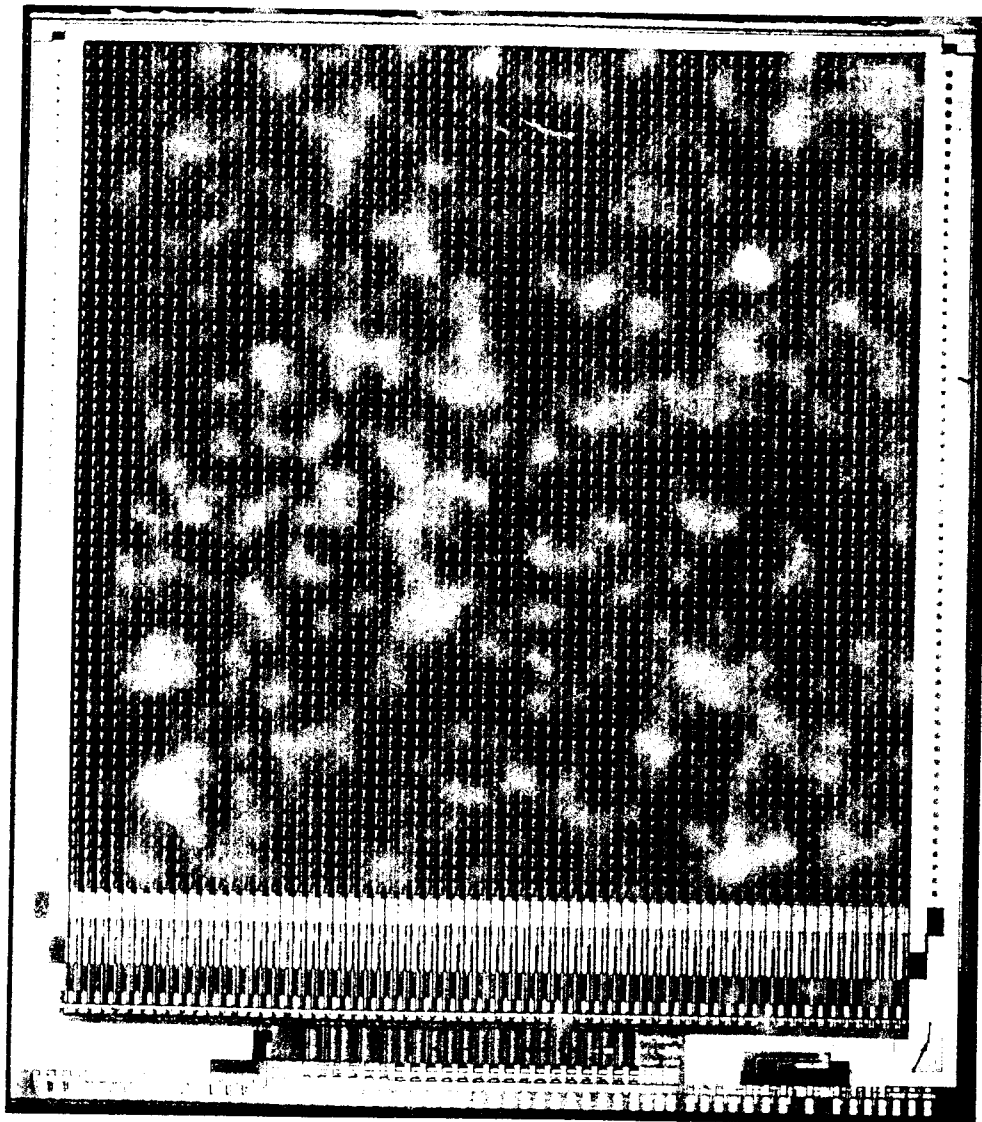
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Photon Counting Chip CERN

PCC1 64 x 64 PIXELS 170 μ m x 170 μ m



1997

Amplifier-Shaper **1 μ m SACMOS**
Comparator **3-bit adjust**
16 bit counter **common electronic shutter**
Dark current compensation per column **10 nA**
Readout **384 μ s**

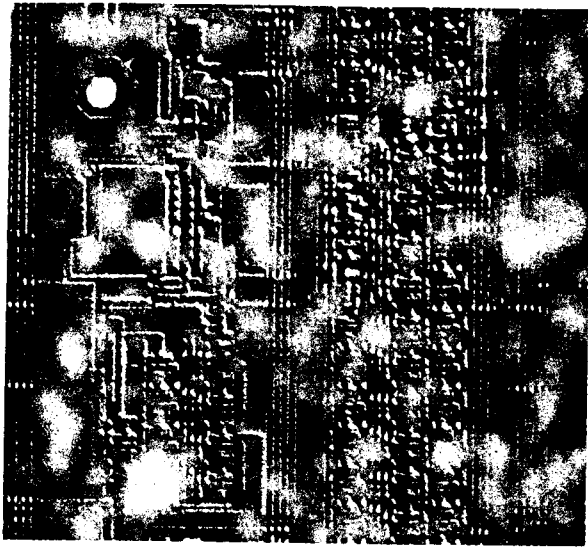


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Photon Counting Chip CERN



170 μ m x 170 μ m

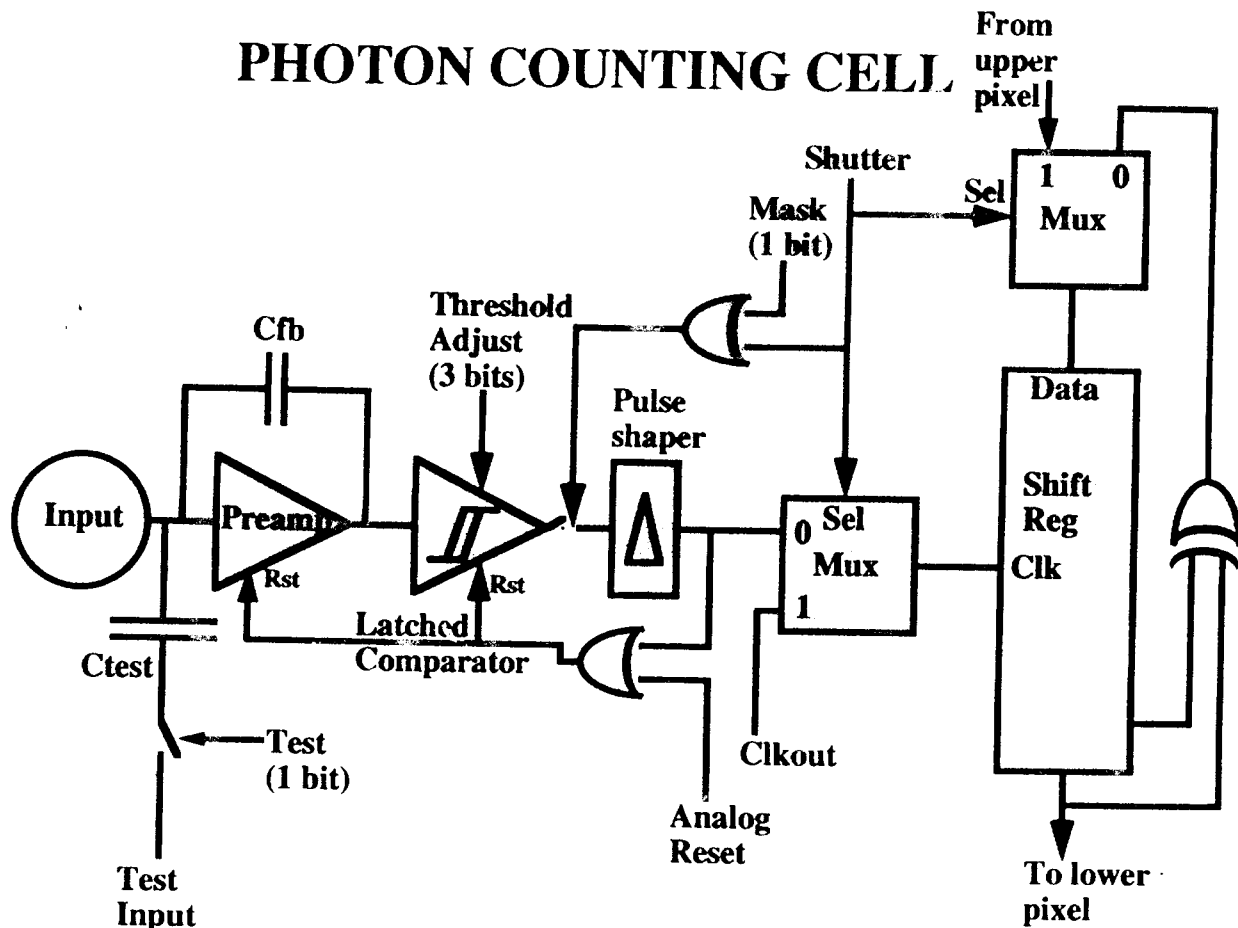
15 - bit COUNTER

STATIC LOGIC

400 transistors

Bumpbonding

Si or GaAs sensor



THRESHOLD ADJUST using 3 bit TRIM



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Photon Counting Chip CERN

SUMMARY

150 ns PEAKING TIME (rate < 5 MHz)
HIGH COUNT RATE

$$\sim 10^9 \text{ s}^{-1}\text{cm}^{-2}$$

Maximum occupancy $\sim 50\%$

ELECTRONIC NOISE $\sim 170 \text{ e}^- \text{ rms}$
DARK CURRENT COMPENSATION

$$10 \text{ nA / pixel}$$

$$30 \mu\text{A cm}^{-2}$$

TEST SIGNAL INDIVIDUAL PIXELS
MASKING of BAD PIXELS
THRESHOLD ADJUSTABLE

$$\sim 120 \text{ e}^- \text{ rms}$$

ALLOWS LOW THRESHOLD

$$\sim 1400 \text{ e}^- \quad 5 \text{ keV}$$

READOUT TIME $384 \mu\text{s}$ per CHIP



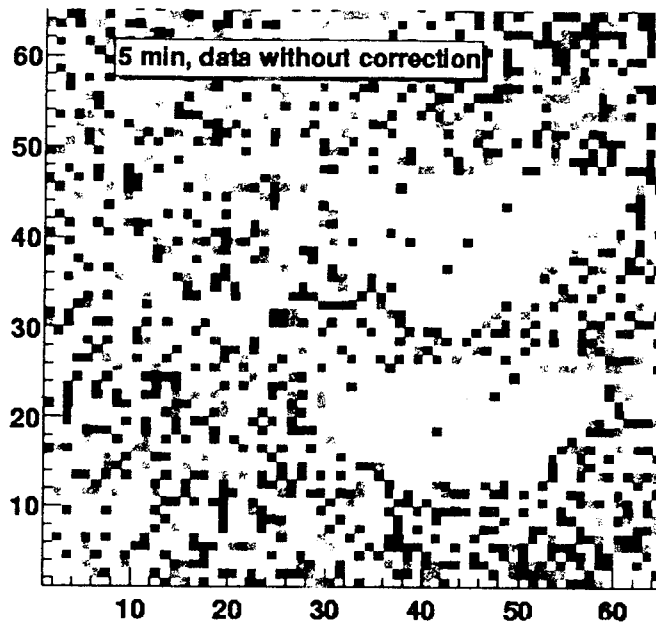
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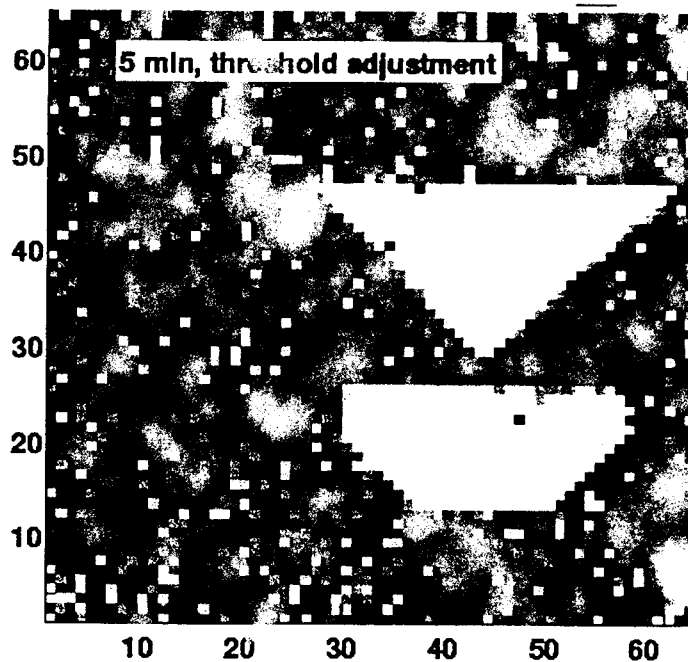


Photon Counting Chip CERN

EFFECT OF THRESHOLD ADJUST



NO ADJUST



WITH

2 PIECES of 100 μm THICK Si : SOURCE ^{55}Fe



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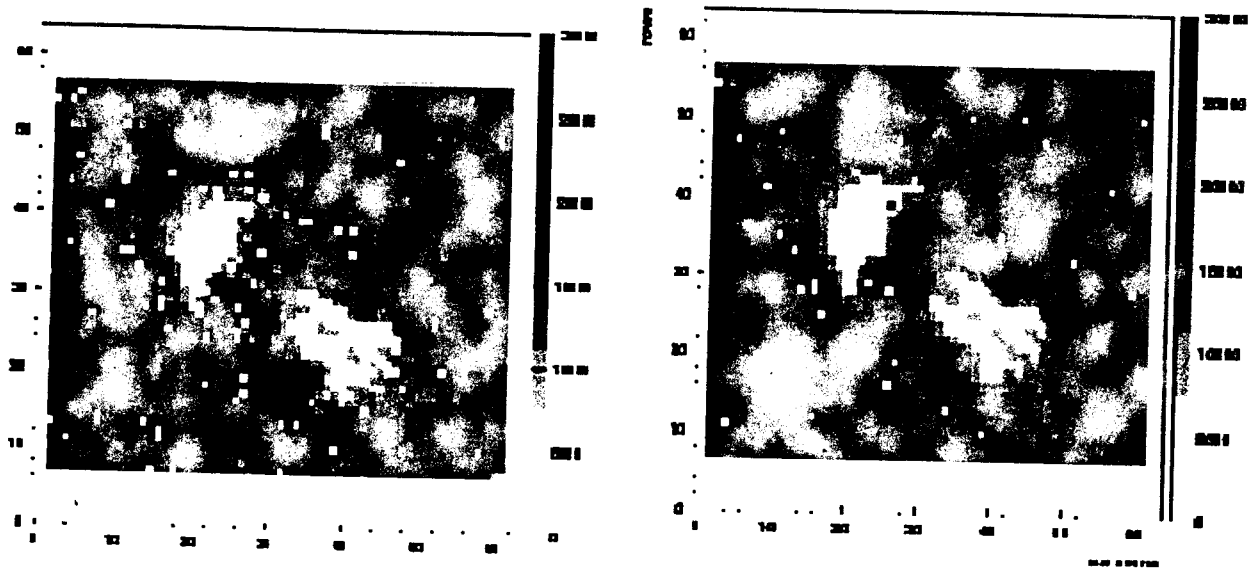
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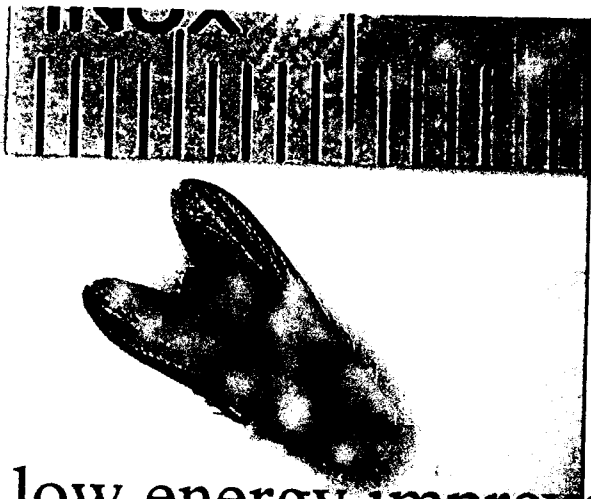
Photon Counting Chip CERN

EFFECT FLAT FIELD CORRECTION

Compensation for inhomogeneity :
source geometry
pixel size, window absorption, etc



5.9 keV : SOURCE ^{55}Fe



low energy improves contrast



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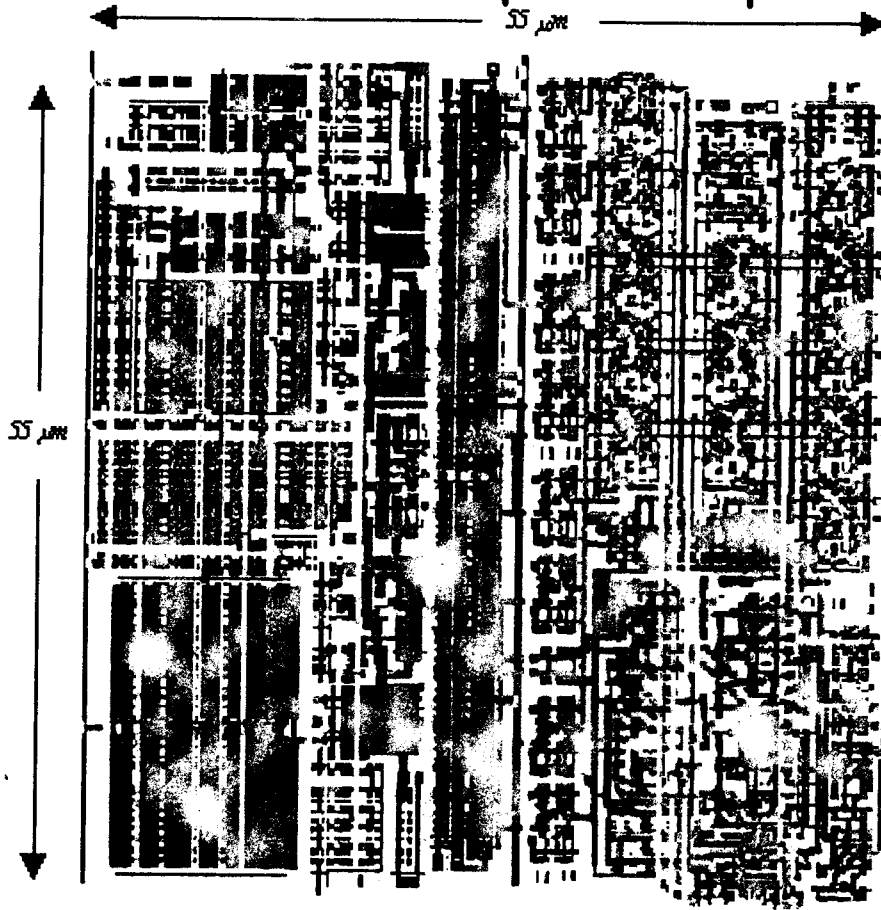
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Photon Counting Chip CERN

Medipix Collaboration

CELL PCC2 $55\mu\text{m} \times 55\mu\text{m}$



+ and - polarity $0.25\mu\text{m}$ CMOS
dark current compensation per pixel
window discriminator
linear range $80\,000\text{ e}^-$
13 bit counter + overflow
count rate $\sim 10^{11}\text{ cm}^{-2}$



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SYNCHROTRON DETECTORS

ANALOG INTEGRATION

SINGLE QUANTA

ADC IN PIXEL

BINARY COUNTING

MULTIPLE THRESHOLDS

MHz COUNTING IN PIXEL

10^{11} cm^{-2}

TIME RESOLUTION

FAST READOUT

CONTIGUOUS TILING

ASSEMBLY without DEAD AREA

EDGE TECHNOLOGY NEEDED



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ASSEMBLY TECHNOLOGY

c.2. Flip chip technology

A flip-chip redistribution technique has been derived from the multilayer thin-film technology developed for high-density MCM interconnects (C22, C390). The technique uses Ni/Au plated copper conductors for redistribution. Benzo cyclo butene (BCB) polymer layers are used as isolation and solder mask layer. Solder bumps are realized by screen printing solder paste, reflow of the solder paste and wafer cleaning (flux removal). A schematic cross-section and picture of a redistributed die are shown in figure 81.

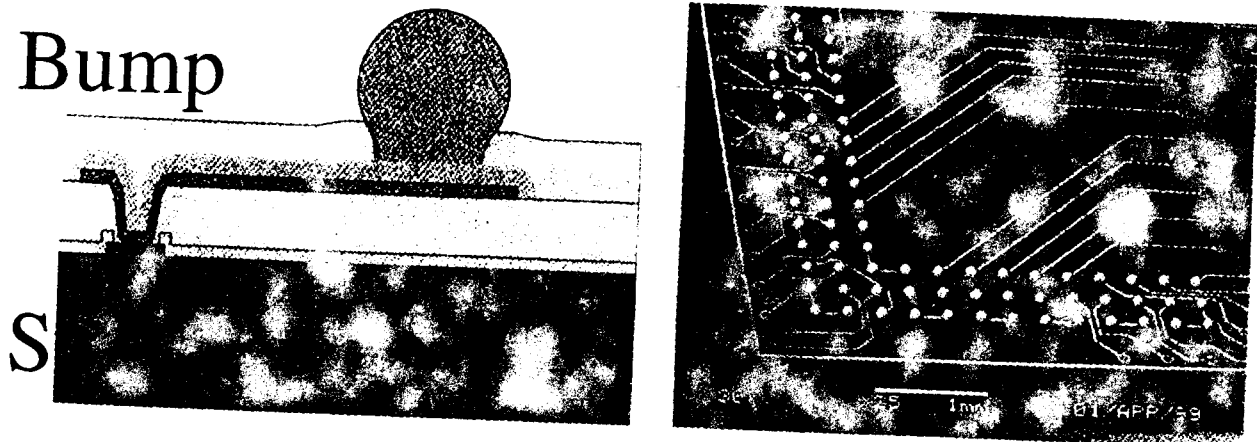


Figure 81: Schematic flip-chip redistribution technique (left) and SEM picture of a redistributed IC (right).

FLIP-CHIP BUMP CONTACT REDISTRIBUTION via MULTI-LAYER STRUCTURE

5 Cu / BCB (Benzo Cyclo Butene)
How Far Can One Go ? several mm ?



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CONCLUSION

CHIP TECHNOLOGY -> NEW DETS

SINGLE QUANTUM PROCESSING

MHz COUNTING IN PIXEL

10^{11} cm^{-2}

FAST PROCESSES RESOLVABLE

CREATE DESIGN KNOW - HOW



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SPECIFIC NEEDS SYNCHROTRON



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